

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)	Docket No.:	020732-97.668 (7493)
)		
Applicants: RATH, Melissa K., et al.)	Conf. No.:	4823
)		
Application No.: 10/792,038)	Art Unit:	1752
)		
Date Filed: March 3, 2004)	Examiner:	LE, Hoa Van
)		
Title: COMPOSITION AND PROCESS FOR)	Customer No.:	24239
POST-ETCH REMOVAL OF)		
PHOTORESIST AND/OR)		
SACRIFICIAL ANTI-REFLECTIVE)		
MATERIAL DEPOSITED ON A)		
SUBSTRATE)		

**AMENDMENT RESPONDING TO SEPTEMBER 15, 2008 OFFICE ACTION AND
REQUEST FOR A ONE-MONTH EXTENSION UNDER 37 CFR §1.136(a) IN UNITED
STATES PATENT APPLICATION NO. 10/792,038**

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This responds to the September 15, 2008 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the September 15, 2008 Office Action are set out in the **Section II (Remarks)** hereof.